

Constantin Vahlas

List of Publications by Year in descending order

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304368

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161
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161
docs citations

161
times ranked

2404
citing authors

#	ARTICLE	IF	CITATIONS
1	Nanoenergetic Materials for MEMS: A Review. Journal of Microelectromechanical Systems, 2007, 16, 919-931.	1.7	416
2	Principles and applications of CVD powder technology. Materials Science and Engineering Reports, 2006, 53, 1-72.	14.8	147
3	Parametric study for the growth of carbon nanotubes by catalytic chemical vapor deposition in a fluidized bed reactor. Carbon, 2002, 40, 1799-1807.	5.4	145
4	A thermodynamic evaluation of four Si-M (M = Mo, Ta, Ti, W) binary systems. Calphad: Computer Coupling of Phase Diagrams and Thermochemistry, 1989, 13, 273-292.	0.7	89
5	Corrosion protection of 304L stainless steel by chemical vapor deposited alumina coatings. Corrosion Science, 2014, 81, 125-131.	3.0	83
6	Temperature-Dependent 4-, 5- and 6-Fold Coordination of Aluminum in MOCVD-Grown Amorphous Alumina Films: A Very High Field ²⁷ Al-NMR study. Journal of Physical Chemistry C, 2013, 117, 21965-21971.	1.5	78
7	CVD-Fabricated Aluminum Oxide Coatings from Aluminum tri-iso-propoxide: Correlation Between Processing Conditions and Composition. Chemical Vapor Deposition, 2007, 13, 23-29.	1.4	52
8	Metallization of polymer composites by metalorganic chemical vapor deposition of Cu: Surface functionalization driven films characteristics. Surface and Coatings Technology, 2013, 230, 254-259.	2.2	47
9	Investigation of the initial deposition steps and the interfacial layer of Atomic Layer Deposited (ALD) Al ₂ O ₃ on Si. Applied Surface Science, 2019, 492, 245-254.	3.1	46
10	Mechanical and barrier properties of MOCVD processed alumina coatings on Ti6Al4V titanium alloy. Surface and Coatings Technology, 2011, 206, 1684-1690.	2.2	45
11	Thermal degradation mechanisms of Nicalon fibre:a thermodynamic simulation. Journal of Materials Science, 1994, 29, 5839-5846.	1.7	37
12	Aluminium tri-iso-propoxide: Shelf life, transport properties, and decomposition kinetics for the low temperature processing of aluminium oxide-based coatings. Surface and Coatings Technology, 2007, 201, 9159-9162.	2.2	36
13	Detailed investigation of the surface mechanisms and their interplay with transport phenomena in alumina atomic layer deposition from TMA and water. Chemical Engineering Science, 2019, 195, 399-412.	1.9	35
14	MOCVD-Processed Ni Films from Nickelocene. Part I: Growth Rate and Morphology. Chemical Vapor Deposition, 1999, 5, 135-142.	1.4	34
15	An experimental and computational analysis of a MOCVD process for the growth of Al films using DMEAA. Surface and Coatings Technology, 2007, 201, 8868-8872.	2.2	34
16	Carbon nanotubes produced by substrate free metalorganic chemical vapor deposition of iron catalysts and ethylene. Carbon, 2001, 39, 443-449.	5.4	33
17	CVD of Pure Copper Films from Amidinate Precursor. Electrochemical and Solid-State Letters, 2011, 14, D26.	2.2	31
18	Fluidization, Spouting, and Metal-Organic CVD of Platinum Group Metals on Powders. Chemical Vapor Deposition, 2002, 8, 127.	1.4	28

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19	Computational Fluid Dynamics simulation of the ALD of alumina from TMA and H ₂ O in a commercial reactor. <i>Chemical Engineering Research and Design</i> , 2018, 132, 795-811.	2.7	26
20	Precursors and operating conditions for the metal-organic chemical vapor deposition of nickel films. <i>Annales De Chimie: Science Des Materiaux</i> , 2000, 25, 81-90.	0.2	25
21	Investigation of the densification mechanisms and corrosion resistance of amorphous silica films. <i>Journal of Non-Crystalline Solids</i> , 2019, 515, 34-41.	1.5	25
22	MOCVD-Processed Ni Films from Nickelocene. Part II: Carbon Content of the Deposits. <i>Chemical Vapor Deposition</i> , 1999, 5, 143-149.	1.4	24
23	Atomic scale structure of amorphous aluminum oxyhydroxide, oxide and oxycarbide films probed by very high field ²⁷ Al nuclear magnetic resonance. <i>Physical Chemistry Chemical Physics</i> , 2017, 19, 8101-8110.	1.3	23
24	Selection of metalorganic precursors for MOCVD of metallurgical coatings: application to Cr-based coatings. <i>Surface and Coatings Technology</i> , 1996, 86-87, 316-324.	2.2	22
25	Chemical vapor deposition of Pd/Cu alloy films from a new single source precursor. <i>Journal of Crystal Growth</i> , 2015, 414, 130-134.	0.7	22
26	Tensions interfaciales et mecanismes de croissance monotectique des alliages immiscibles binaires. <i>Scripta Metallurgica</i> , 1984, 18, 1-6.	1.2	21
27	LPCVD WSi ₂ Films Using Tungsten Chlorides and Silane. <i>Journal of the Electrochemical Society</i> , 1993, 140, 475-484.	1.3	21
28	Investigation of Nickelocene Decomposition during Chemical Vapor Deposition of Nickel. <i>Journal of the Electrochemical Society</i> , 2000, 147, 1443.	1.3	21
29	Chemical Vapor Deposition of Iron, Iron Carbides, and Iron Nitride Films from Amidinate Precursors. <i>Journal of the Electrochemical Society</i> , 2010, 157, D454.	1.3	21
30	CVD and Powders: A Great Potential to Create New Materials. <i>Chemical Vapor Deposition</i> , 2007, 13, 443-445.	1.4	20
31	Reaction and Transport Interplay in Al MOCVD Investigated Through Experiments and Computational Fluid Dynamic Analysis. <i>Journal of the Electrochemical Society</i> , 2010, 157, D633.	1.3	20
32	TiO ₂ nanotree films for the production of green H ₂ by solar water splitting: From microstructural and optical characteristics to the photocatalytic properties. <i>Applied Surface Science</i> , 2019, 494, 1127-1137.	3.1	20
33	A Thermodynamic Approach to the CVD of Chromium and of Chromium Carbides Starting from Cr(C ₆ H ₆) ₂ . <i>Chemical Vapor Deposition</i> , 1998, 04, 69-76.	1.4	20
34	A thermodynamic evaluation of the Ti-N system. <i>Thermochimica Acta</i> , 1991, 180, 23-37.	1.2	19
35	A Delivery System for Precursor Vapors Based on Sublimation in a Fluidized Bed. <i>Chemical Vapor Deposition</i> , 2007, 13, 123-129.	1.4	19
36	Multiscale modeling and experimental analysis of chemical vapor deposited aluminum films: Linking reactor operating conditions with roughness evolution. <i>Chemical Engineering Science</i> , 2016, 155, 449-458.	1.9	19

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37	CVD of Pure Copper Films from a Novel Amidinate Precursor. ECS Transactions, 2009, 25, 581-586.	0.3	18
38	Amorphous Alumina Coatings: Processing, Structure and Remarkable Barrier Properties. Journal of Nanoscience and Nanotechnology, 2011, 11, 8387-8391.	0.9	18
39	Thermal behaviour of CpCuPEt3 in gas phase and Cu thin films processing. Surface and Coatings Technology, 2007, 201, 9131-9134.	2.2	16
40	Conformity of Aluminum Thin Films Deposited onto Micro-Patterned Silicon Wafers by Pulsed Laser Deposition, Magnetron Sputtering, and CVD. Chemical Vapor Deposition, 2011, 17, 366-374.	1.4	16
41	Direct liquid injection chemical vapor deposition of ZrO ₂ films from a heteroleptic Zr precursor: interplay between film characteristics and corrosion protection of stainless steel. Journal of Materials Research and Technology, 2021, 13, 1599-1614.	2.6	16
42	Thermodynamics of the Y-Ba-Cu-C-O-H System: Application to the Organometallic Chemical Vapor Deposition of the YBa ₂ Cu ₃ O _{7-x} Phase. Journal of the American Ceramic Society, 1992, 75, 2679-2686.	1.9	15
43	On the thermal degradation of Iox-M tyranno® fibres. Journal of the European Ceramic Society, 1995, 15, 445-453.	2.8	15
44	Electrochemical Behavior of Chemical Vapor Deposited Protective Aluminum Oxide Coatings on Ti6242 Titanium Alloy. Electrochemical and Solid-State Letters, 2008, 11, C55.	2.2	15
45	Local Kinetic Modeling of Aluminum Oxide Metal-Organic CVD From Aluminum Triisopropoxide. Chemical Vapor Deposition, 2011, 17, 181-185.	1.4	15
46	Volatile Heterobimetallic Complexes from Pd ^{II} and Cu ^{II} Diketonates: Structure, Magnetic Anisotropy, and Thermal Properties Related to the Chemical Vapor Deposition of Cu _{1-x} Pd Thin Films. ChemPlusChem, 2015, 80, 1457-1464.	1.3	15
47	MOCVD Processed Ni Films from Nickelocene. Part III: Gas Phase Study and Deposition Mechanisms. Chemical Vapor Deposition, 1999, 5, 281-290.	1.4	13
48	Al-Pt MOCVD coatings for the protection of Ti6242 alloy against oxidation at elevated temperature. Surface and Coatings Technology, 2005, 200, 1413-1417.	2.2	13
49	Mass Spectrometric Monitoring of the Gas Phase during the CVD of Copper from Copper Cyclopentadienyl Triethylphosphine. Chemical Vapor Deposition, 2012, 18, 209-214.	1.4	13
50	Experimental and computational investigation of chemical vapor deposition of Cu from Cu amidinate. Surface and Coatings Technology, 2013, 230, 273-278.	2.2	13
51	Liquid and Solid Precursor Delivery Systems in Gas Phase Processes. Recent Patents on Materials Science, 2015, 8, 91-108.	0.5	13
52	Chemical vapor deposition of low reflective cobalt (II) oxide films. Applied Surface Science, 2016, 360, 540-546.	3.1	13
53	Investigation of reaction mechanisms in the chemical vapor deposition of Al from DMEAA. Chemical Engineering Science, 2018, 177, 464-470.	1.9	13
54	In- and out-plane transport properties of chemical vapor deposited TiO ₂ anatase films. Journal of Materials Science, 2021, 56, 10458-10476.	1.7	13

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55	A Thermodynamic Approach to the CVD of Chromium and of Chromium Carbides Starting from Cr(C ₆ H ₆) ₂ . <i>Chemical Vapor Deposition</i> , 1998, 4, 69-76.	1.4	12
56	Low Temperature Metallorganic Chemical Vapor Deposition Routes to Chromium Metal Thin Films Using Bis(benzene)chromium. <i>Journal of the Electrochemical Society</i> , 1999, 146, 3716-3723.	1.3	12
57	Chemical vapor deposition of ruthenium on NiCoCrAlYTa powders followed by thermal oxidation of the sintered coupons. <i>Surface and Coatings Technology</i> , 2003, 163-164, 44-49.	2.2	12
58	Phase Transformations of Metallorganic Chemical Vapor Deposition Processed Alumina Coatings Investigated by In Situ Deflection. <i>Journal of the Electrochemical Society</i> , 2007, 154, P63.	1.3	12
59	Decomposition Schemes of Copper(I) β -Diisopropylacetamidinate During Chemical Vapor Deposition of Copper. <i>Journal of Nanoscience and Nanotechnology</i> , 2011, 11, 8198-8201.	0.9	12
60	Al-Cu intermetallic coatings processed by sequential metalorganic chemical vapour deposition and post-deposition annealing. <i>Applied Surface Science</i> , 2012, 258, 6425-6430.	3.1	12
61	Study on Structural and Thermal Characteristics of Heteroleptic Yttrium Complexes as Potential Precursors for Vapor Phase Deposition. <i>European Journal of Inorganic Chemistry</i> , 2020, 2020, 3587-3596.	1.0	12
62	A thermodynamic and experimental approach to TaSi ₂ chemical vapour deposition. <i>Thin Solid Films</i> , 1989, 177, 189-206.	0.8	11
63	Low Temperature MOCVD-Processed Alumina Coatings. <i>Advances in Science and Technology</i> , 2006, 45, 1184-1193.	0.2	11
64	Toward a computational and experimental model of a poly-epoxy surface. <i>Applied Surface Science</i> , 2015, 324, 605-611.	3.1	11
65	Morphological, structural, optical, and electrical study of nanostructured thin films: Charge transport mechanism of p-type Co ₃ O ₄ . <i>Materials Chemistry and Physics</i> , 2020, 240, 122059.	2.0	11
66	Thermodynamic study of the thermal degradation of SiC-based fibres: Influence of SiC grain size. <i>Journal of Materials Science Letters</i> , 1995, 14, 1558-1561.	0.5	10
67	Thermodynamic study, compositional and electrical characterization of LPCVD SiO ₂ films grown from TEOS/N ₂ O mixtures. <i>Microelectronics Reliability</i> , 1998, 38, 265-269.	0.9	10
68	Transmission electron microscopy of Re and Ru films deposited on NiCoCrAlYTa powders. <i>Scripta Materialia</i> , 2004, 51, 699-703.	2.6	10
69	Hydrodynamic study of fine metallic powders in an original spouted bed contactor in view of chemical vapor deposition treatments. <i>Powder Technology</i> , 2006, 165, 65-72.	2.1	10
70	Iron Thin Films from Fe(CO) ₅ and FeCp ₂ ·H ₂ O under Atmospheric Pressure. <i>Journal of the Electrochemical Society</i> , 2006, 153, G1025.	1.3	10
71	Chemical vapour deposition and atomic layer deposition of amorphous and nanocrystalline metallic coatings: Towards deposition of multimetallic films. <i>Journal of Alloys and Compounds</i> , 2010, 504, S422-S424.	2.8	10
72	Alumina thin films prepared by direct liquid injection chemical vapor deposition of dimethylaluminum isopropoxide: a process-structure investigation. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2015, 12, 989-995.	0.8	10

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73	Combined Macro/Nanoscale Investigation of the Chemical Vapor Deposition of Fe from Fe(CO) ₅ . Advanced Materials Interfaces, 2017, 4, 1601185.	1.9	10
74	Thermodynamic Approach to the Oxidation of Hi-Nicalon Fiber. Journal of the American Ceramic Society, 1999, 82, 2514-2516.	1.9	9
75	Process-Structure-Properties relationship in direct liquid injection chemical vapor deposition of amorphous alumina from aluminum triisopropoxide. Physica Status Solidi C: Current Topics in Solid State Physics, 2015, 12, 944-952.	0.8	9
76	Metallization of carbon fiber reinforced polymers: Chemical kinetics, adhesion, and properties. Surface and Coatings Technology, 2016, 308, 62-69.	2.2	9
77	Development of a kinetic model for the moderate temperature chemical vapor deposition of SiO ₂ films from tetraethyl orthosilicate and oxygen. AIChE Journal, 2018, 64, 3958-3966.	1.8	9
78	Large temperature range model for the atmospheric pressure chemical vapor deposition of silicon dioxide films on thermosensitive substrates. Chemical Engineering Research and Design, 2020, 161, 146-158.	2.7	9
79	Thermodynamic Study, Composition, and Microstructure of Low-Pressure Chemical Vapor Deposited Silicon Dioxide Films Grown from TEOS/NO ₂ Mixtures. Journal of the Electrochemical Society, 145, 1310-1317.	1.8	9
80	Investigation of interfacial reactivity in composite materials. Materials Science & Engineering A: Structural Materials: Properties, Microstructure and Processing, 1999, 259, 269-278.	2.6	8
81	Shape Optimization of a Showerhead System for the Control of Growth Uniformity in a MOCVD Reactor Using CFD-based Evolutionary Algorithms. ECS Transactions, 2009, 25, 1053-1060.	0.3	8
82	Temperature Dependent 4-, 5- and 6-Fold Coordination of Aluminum in MOCVD-Grown Amorphous Alumina Films: From Local Coordination to Material Properties. Advances in Science and Technology, 0, , .	0.2	8
83	A Process-Structure Investigation of Aluminum Oxide and Oxycarbide Thin Films prepared by Direct Liquid Injection CVD of Dimethylaluminum Isopropoxide (DMAI). Chemical Vapor Deposition, 2015, 21, 343-351.	1.4	8
84	Chemical Vapor Deposition of Al ₁₃ Fe ₄ Highly Selective Catalytic Films for the Semi-Hydrogenation of Acetylene. Physica Status Solidi (A) Applications and Materials Science, 2018, 215, 1700692.	0.8	8
85	Tunable SiO ₂ to SiO _x C _y H films by ozone assisted chemical vapor deposition from tetraethylorthosilicate and hexamethyldisilazane mixtures. Surface and Coatings Technology, 2021, 407, 126762.	2.2	8
86	MOCVD processed platinum-aluminum coatings on titanium alloys. Surface and Coatings Technology, 2004, 188-189, 49-54.	2.2	7
87	Microstructure of Metallorganic Chemical Vapor Deposited Aluminum Coatings on Ti6242 Titanium Alloy. Journal of the Electrochemical Society, 2007, 154, D538.	1.3	7
88	Surface-driven, one-step chemical vapor deposition of β -Al ₄ Cu ₉ complex metallic alloy film. Applied Surface Science, 2013, 283, 788-793.	3.1	7
89	Amorphous Alumina Coatings on Glass Bottles Using Direct Liquid Injection MOCVD for Packaging Applications. Advances in Science and Technology, 0, , .	0.2	7
90	Investigation of the kinetics of the chemical vapor deposition of aluminum from dimethylethylamine alane: experiments and computations. Physica Status Solidi C: Current Topics in Solid State Physics, 2015, 12, 923-930.	0.8	7

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91	Modeling a MOCVD process to apply alumina films on the inner surface of bottles. Surface and Coatings Technology, 2015, 275, 167-175.	2.2	7
92	Amorphous alumina thin films deposited on titanium: Interfacial chemistry and thermal oxidation barrier properties. Physica Status Solidi (A) Applications and Materials Science, 2016, 213, 470-480.	0.8	7
93	Nanocomposite thin film of Ag nanoparticles embedded in amorphous Al ₂ O ₃ on optical sensors windows: Synthesis, characterization and targeted application towards transparency and anti-biofouling. Surface and Coatings Technology, 2017, 328, 371-377.	2.2	7
94	Influence of Hydrogen Pressure on the Properties of CVD Tungsten Silicide Films. Journal of the Electrochemical Society, 1995, 142, 1608-1614.	1.3	6
95	Thermodynamic Study of the Formation of W_2C and W_6C by Combustion or Pyrolysis. Journal of the Electrochemical Society, 1999, 146, 2752-2761.	1.3	6
96	Platinum Protective Coatings Processed by Organometallic CVD. Chemical Vapor Deposition, 2008, 14, 103-106.	1.4	6
97	Thermal decomposition of tungsten hexacarbonyl: CVD of W-containing films under Pd codeposition and VUV assistance. Physica Status Solidi C: Current Topics in Solid State Physics, 2015, 12, 1047-1052.	0.8	6
98	$\text{N}_2\text{-NH}_3$ plasma pre-treatment of silicon substrate enhances the initial growth and restricts the substrate oxidation during alumina ALD. Journal of Applied Physics, 2019, 126, 125305.	1.1	6
99	Toward the Improvement of the Microstructure of Chemical Vapor Deposited Aluminum on Silicon Carbide. Journal of the Electrochemical Society, 2001, 148, C583.	1.3	5
100	Protective Alumina Coatings by Low Temperature Metalorganic Chemical Vapour Deposition. Advanced Materials Research, 2007, 23, 245-248.	0.3	5
101	Iron Amidinates as Precursors for the MOCVD of Iron Containing Thin Films. ECS Transactions, 2009, 25, 181-188.	0.3	5
102	Mass Spectrometry as a Tool to Study MOCVD Process. ECS Transactions, 2009, 25, 1301-1308.	0.3	5
103	CHEMICAL VAPOR DEPOSITION OF METALS: FROM UNARY SYSTEMS TO COMPLEX METALLIC ALLOYS. Book Series on Complex Metallic Alloys, 2010, , 49-81.	0.1	5
104	Amorphous Alumina Barrier Coatings on Glass: MOCVD Process and Hydrothermal Aging. Advanced Materials Interfaces, 2016, 3, 1600014.	1.9	5
105	Efficient, durable protection of the Ti6242S titanium alloy against high-temperature oxidation through MOCVD processed amorphous alumina coatings. Journal of Materials Science, 2020, 55, 4883-4895.	1.7	5
106	Chemical vapor deposition of Cu films from copper(I) cyclopentadienyl triethylphosphine: Precursor characteristics and interplay between growth parameters and films morphology. Thin Solid Films, 2020, 701, 137967.	0.8	5
107	Thermodynamic and Experimental Modeling of Interfacial Reactivity in Metal Matrix Composites. Key Engineering Materials, 1997, 127-131, 359-368.	0.4	4
108	Spouted bed metallorganic chemical vapor deposition of ruthenium on NiCoCrAlYTa powders. European Physical Journal Special Topics, 2001, 11, Pr3-1117-Pr3-1123.	0.2	4

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109	Complex Pt/Al ₂ O ₃ materials for small catalytic systems. <i>Surface and Coatings Technology</i> , 2007, 201, 9195-9199.	2.2	4
110	Mechanical and Surface Properties of Chemical Vapor Deposited Protective Aluminium Oxide Films on TA6V Alloy. <i>Advances in Science and Technology</i> , 0, , .	0.2	4
111	Monitoring microstructure and phase transitions in thin films by high-temperature resistivity measurements. <i>Surface and Interface Analysis</i> , 2012, 44, 1162-1165.	0.8	4
112	Black Co oxides coatings for thermosensitive polymer surfaces by low-temperature DLI-MOCVD. <i>Surface and Coatings Technology</i> , 2018, 349, 941-948.	2.2	4
113	Network hydration, ordering and composition interplay of chemical vapor deposited amorphous silica films from tetraethyl orthosilicate. <i>Journal of Materials Research and Technology</i> , 2021, 13, 534-547.	2.6	4
114	An innovative kinetic model allowing insight in the moderate temperature chemical vapor deposition of silicon oxynitride films from tris(dimethylsilyl)amine. <i>Chemical Engineering Journal</i> , 2022, 431, 133350.	6.6	4
115	Adsorption-induced solid-liquid interfacial roughening in Zn alloys. <i>Journal of Crystal Growth</i> , 1988, 92, 253-258.	0.7	3
116	Low pressure chemical vapor deposition from TEOS-NH ₃ mixtures: thermochemical study of the process considering kinetic data. <i>Microelectronics Reliability</i> , 1999, 39, 303-309.	0.9	3
117	Evaluation of Al ₂ O ₃ /MOCVD Coating for Titanium Alloys Protection under Severe Conditions at High Temperature. <i>Materials Science Forum</i> , 0, 595-598, 719-724.	0.3	3
118	Residual Stress Mechanisms in Aluminium Oxide Films Grown by MOCVD. <i>ECS Transactions</i> , 2009, 25, 1309-1315.	0.3	3
119	Microstructural characterization of Ru-doped NiCoCrAlYTa coupons treated by thermal oxidation. <i>Corrosion Science</i> , 2009, 51, 2192-2196.	3.0	3
120	Amorphous Alumina Films Efficiently Protect Ti6242S against Oxidation and Allow Operation above 600 Å°C. <i>Materials Science Forum</i> , 0, 941, 1846-1852.	0.3	3
121	Engineering structure and functionalities of chemical vapor deposited photocatalytic titanium dioxide films through different types of precursors. <i>CrystEngComm</i> , 2021, 23, 3681-3692.	1.3	3
122	An innovative GC-MS, NMR and ESR combined, gas-phase investigation during chemical vapor deposition of silicon oxynitrides films from tris(dimethylsilyl)amine. <i>Physical Chemistry Chemical Physics</i> , 2021, 23, 10560-10572.	1.3	3
123	Engineering Copper Adhesion on Poly-Epoxy Surfaces Allows One-Pot Metallization of Polymer Composite Telecommunication Waveguides. <i>Coatings</i> , 2021, 11, 50.	1.2	3
124	Interest of thermochemical data bases linked to complex equilibria calculation codes for practical applications. <i>Journal De Chimie Physique Et De Physico-Chimie Biologique</i> , 1993, 90, 281-293.	0.2	3
125	Chemical vapor deposition of pyrolytic carbon on polished substrates. <i>European Physical Journal Special Topics</i> , 1993, 03, C3-563-C3-570.	0.2	3
126	Experimental approaches to simulating interfacial reactions in metal matrix composites. <i>Metallurgical and Materials Transactions A: Physical Metallurgy and Materials Science</i> , 1998, 29, 1347-1355.	1.1	2

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127	Microstructural and mechanical properties of powder NiCoCrAlYTa superalloy consolidated by spark plasma sintering. , 2009, , .		2
128	Functionalization of, and Deposition on Complexâ€Shaped Surfaces: Vacuum Processes, Materials, Models, Challenges, and Methods. Chemical Vapor Deposition, 2011, 17, 274-278.	1.4	2
129	Ballistic and molecular dynamics simulations of aluminum deposition in micro-trenches. Thin Solid Films, 2013, 536, 115-123.	0.8	2
130	Barrier properties and hydrothermal aging of amorphous alumina coatings applied on pharmaceutical vials. Surface and Coatings Technology, 2021, 425, 127711.	2.2	2
131	Driving Force for Free-Carbon Incorporation in Chromium Carbide Films Processed by MOCVD. Chemical Vapor Deposition, 1998, 04, 96-99.	1.4	2
132	Etude de lâ€™adsorption et de la tension interfaciale solide-liquide de systÃˆmes ternaires Ã base de zinc. Journal De Chimie Physique Et De Physico-Chimie Biologique, 1983, 80, 515-521.	0.2	2
133	Composition and magnetic properties of MOCVD processed thin films from nickelocene. European Physical Journal Special Topics, 1999, 09, Pr8-1099-Pr8-1106.	0.2	2
134	Mass Spectrometric Study of the Gas Phase During Chemical Vapor Deposition of Pyrolytic Carbon. European Physical Journal Special Topics, 1995, 05, C5-89-C5-96.	0.2	2
135	Critical Level of Nitrogen Incorporation in Silicon Oxynitride Films: Transition of Structure and Properties, toward Enhanced Anticorrosion Performance. ACS Applied Electronic Materials, 0, , .	2.0	2
136	Processing of Silicon Oxides Thin Films by Thermal LPCVD Starting from Teos Mixtures. Materials Research Society Symposia Proceedings, 1996, 446, 291.	0.1	1
137	Driving Force for Free-Carbon Incorporation in Chromium Carbide Films Processed by MOCVD. Chemical Vapor Deposition, 1998, 4, 96-99.	1.4	1
138	Adaptation of a dry metalorganic chemical vapor deposition metallization process to a wet chemical pretreatment of polymers. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2017, 35, 061101.	0.9	1
139	Beyond surface nanoindentation: Combining static and dynamic nanoindentation to assess intrinsic mechanical properties of chemical vapor deposition amorphous silicon oxide (SiOx) and silicon oxycarbide (SiOxCy) thin films. Thin Solid Films, 2021, 735, 138844.	0.8	1
140	MOCVD Processed Ni Films from Nickelocene. Part III: Gas Phase Study and Deposition Mechanisms. , 1999, 5, 281.		1
141	Growth of carbon nanotubes by fluidized bed catalytic chemical vapor deposition. European Physical Journal Special Topics, 2002, 12, 93-98.	0.2	1
142	CHEMICAL VAPOR DEPOSITION OF TaSi2 AND WSi2 AT ATMOSPHERIC PRESSURE FROM IN SITU PREPARED METAL CHLORIDES. Journal De Physique Colloque, 1989, 50, C5-557-C5-563.	0.2	1
143	MONITORING COMPOSITION AND STRUCTURE OF MOCVD ZrO2-BASED MULTICOMPONENT FILMS BY INNOVATIVE MIXED METAL-ORGANIC PRECURSORS. Journal of Structural Chemistry, 2020, 61, 1729-1739.	0.3	1
144	Single-source heterometallic precursors to MOCVD Pd Cu alloy films for energy and catalysis applications. , 2022, , 453-472.		1

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145	Chemical vapor deposition of refractory metal silicides. Applied Surface Science, 1989, 38, 407.	3.1	0
146	Déposition de Cr à basse température par MOCVD: inhibition de l'incorporation du carbone. Annales De Chimie: Science Des Matériaux, 1998, 23, 681-693.	0.2	0
147	Thermochemistry of Silicon Lpcvd Revisited with Kinetic Data. Materials Research Society Symposia Proceedings, 1998, 507, 951.	0.1	0
148	Processing of Pure Ni Mocvd Films. Materials Research Society Symposia Proceedings, 1998, 514, 491.	0.1	0
149	Crystallographic Analysis of Cvd Films by Using X-Ray Polychromatic Radiation. Materials Research Society Symposia Proceedings, 1998, 524, 121.	0.1	0
150	Low pressure chemical vapor deposition of silicon oxynitride films using tetraethylorthosilicate, dichlorosilane and ammonia mixtures. European Physical Journal Special Topics, 2001, 11, Pr3-231-Pr3-238.	0.2	0
151	Thermodynamic study and characterization of low pressure chemically vapor deposited silicon oxynitride films from tetraethylorthosilicate, dichlorosilane and ammonia gas mixtures. Thin Solid Films, 2003, 429, 77-83.	0.8	0
152	EUROCVD-15. Chemical Vapor Deposition, 2006, 12, 649-654.	1.4	0
153	A Comprehensive Insight in the MOCVD of Aluminum through Interaction between Reactive Transport Modeling and Targeted Growth Experiments. ECS Transactions, 2009, 25, 99-106.	0.3	0
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